### PATENT COOPERATION TREATY

From the NTERNA	TIONAL SEARCHING AUT	HORITY		REC'D 0.2 AUG 2005
To:				"D''
AN, San	ng Jeong			WIPO
` 512-190 Kannggi	6 221, Gumi-dong, Bundang-g i-do 463-715 Republic of Kores	u Seongnam-si,	WR INTERNATI	ITTEN OPINION OF THE ONAL SEARCHING AUTHORITY
Kyunggi	1-00 405-715 Republic of Horo.			(PCT Rule 43bis.1)
		, <b></b>	;	(ICI Mule 4001012)
			Date of mailing (day/month/year)	22 JULY 2005 (22.07.2005)
Applicar	nt's or agent's file reference		FOR FURTHER A	CTION
Qut43-1				See paragraph 2 below
Internation	onal application No.	International filing date	(day/month/year)	Priority date(day/month/year)
PCT/	KR2005/000895	25 MARCH 2005		25 MARCH 2004 (25.03.2004)
Internation	onal Patent Classification (IPC)	or both national classification	ation and IPC	
IPC7 H	H01L 33/00			
Applicate <b>LUXE</b>	LLENT CO., LTD. et a	1		
		Laine to the following ite	me!	
1. This	s opinion contains indications re		ms.	
	Box No. I Basis of the opinion  Box No. II Priority  Box No. III Non-establishment of opinion with regard to novelty, inventive step and industrial applicability			
				e step and industrial applicability
		•	Ha to noverty, hivehave	o stop tale modeling opposition
		of invention		
	Box No. V Reasoned state citations and c	tement under Rule 43bis. 1 explanations supporting su	(a)(i) with regard to no ach statement	velty, inventive step or industrial applicability;
	Box No. VI Certain document	ments cited		
	Box No. VII Certain defe	cts in the international app	plication	
	Box No. VIII Certain obser	vations on the internation	al application .	
2. FUI	RTHER ACTION		to this eminion will be	considered to be a written opinion of the
Inte othe opii	ernational Preliminary Examinir er than this one to be the IPEA a nions of this International Searc	ng Authority ("IPEA") exc and the chosen IPEA has r thing Authority will not be	notified the International so considered.	considered to be a written opinion of the pply where the applicant chooses an Authority al Bureau under Rule 66.1bis(b) that written
IPE of I	his opinion is, as provided abov EA a written reply together, whe Form PCT/ISA/220 or before the further options, see Form PCT	re appropriate, with amen expiration of 22 months	iaments, delote uie exp	the applicant is invited to submit to the iration of 3 months from the date of mailing whichever expires later.
3. For	r further details, see notes to For	rm PCT/ISA/220.		

Name and mailing address of the ISA/KR

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Korean Intellectual Property Office
920 Dunsan-dong, Seo-gu, Daejeon 302-701,
Republic of Korea

Facsimile No. 82-42-472-7140

Authorized officer

KIM, Dong Yup

Telephone No. 82-42-481-5749



International application No.

PCT/KR2005/000895

	Basis of this opinion		
	•		age in
which	it was filed, unless otherwise		
	_ , v	lished on the basis of a translation from the original language into the following language which is the language of a translation furnished for the purposes of international sear	guage rch (under
	Rules 12.3 and 23.1(b)).	v v v in the important application and necess:	ery to the
Vith laime	regard to any nucleotide and invention, this opinion has	and/or amino acid sequence disclosed in the international application and necessals been established on the basis of:	
. typ	e of material	·	
	a sequence listing table(s) related to the sequence	uence listing	
o. for	mat of material		
<u> </u>	in wirtten format in computer readable form	m	
	<b>-</b>		
. time	e of filing/furnishing  contained in the internati	ional application as filed.	
	filed together with the in	iternational application in computer readable form.	
	furnished subsequently to	to this Authority for the purposes of search.	• •
	and the state of the state of	more than one version or copy of a sequence listing and/or table relating thereto has	been
	In addition, in the case that i	red statements that the information in the subsequent or additioanl copies is identical	to that
	filed or rumished, the requir	does not go beyond the application as filed, as appropriate, were furnished.	
1	in the application as thed or	doos not go out one and apr	•
Addit	tional comments:		
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International application No. PCT/KR2005/000895

Box No. V Reasoned statement under Rule 43bis.1(a)(i) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

Statement	1 20	YES
Novelty (N)	Claims 1-20	
	Claims NONE	NO
Inventive step (IS)	Claims 1-20	YES
Involving grap (12)	Claims NONE	NO
Industrial applicability (IA)	Claims 1-20	YES
madatiat approcessory (==)	Claims NONE	NO NO

### 2. Citations and explanations:

1) Reference is made to the following documents:

D1: JP 9-307190 A

D2: JP 9-260726 A

D3: JP 9-326508 A

D4: JP 2000-101135 A D5: WO 2005053042 A1

### Novelty and Inventive Step

The present application is related to a 3-5 light emitting device comprising at least: a n-typed GaN based layer; an active layer; a first p-typed GaN based layer; a carboncontaining layer (SICN or SiC or CN layer); a second p-typed GaN based layer; and a p-electrode.

D1 discloses a semiconductor luminous element comprising: a n-GaN based buffer layer; a n-AlGaN clad layer; a n-GaN optical waveguide layer; an InGaN/InGaN distortion multiple quantum well activation layer;, a p-GaN optical waveguide layer; a p-AlGaN first clad layer; a n-A1GaN current prevention layer having a striped current implantation window; a p-AlGaN second clad layer;, a p-GaN cap layer; and a p-SiC contact layer. Thereafter, a p-side electrode is formed on the p-SiC contact layer.

But, D1 is different from this application in a point that there is no GaN based layer on a p-SiC layer.

D2 discloses a GaN based light emitting device in which an electrode at the p-side is formed through a p-typed GaN layer, a first contact layer, and a high-concentration ptyped H-SiC layer. Therefore the p-electrode is not brought into direct contact with a p-type AlGaN clad layer. Due to this structure, a contact resistance between the electrode and the SiC layer is small and a forward voltage can be lowered.

But, D2 is different from this application in a point that there is no GaN based layer on a p-typed SiC layer.

- continued -

International application No.

PCT/KR2005/000895

#### Supplemental Box

In case the space in any of the preceding boxes is not sufficient.

Continuation of:

BOX V.

D3 discloses a light emitting device containing a P-GaN layer, and a carbon added p-AlN layer, and a p-GalnN layer doped with magnesium and a p-electrode. But there is no description for SICN layer on the p-contact(or clad) layer in D3.

In D4, an MgN contact layer consisting of a compound of magnesium with nitrogen formed on the surface of the p-type layer is introduced to a compound semiconductor device. For improving the characteristics of the semiconductor device, carbon to act as an acceptor in a III-V compound semiconductor layer is added to the p-type layer.

D5 discloses a method for forming GaN-based nitride layer to enhance the cohesion of a SiC buffer layer and a GaN-based nitride layer by forming a wetting layer on the SiC buffer layer.

None of the documents D1-D5 refer to a 3-5 light emitting device comprising: a n-typed GaN based layer; an active layer; a first p-typed GaN based layer; a carbon-containing layer; and a second p-typed GaN based layer formed successively.

D1-D5 are thus considered to be little relevant to the present application.

Compared with the prior arts as cited in the International Search Report, the present invention (claims 1-20) is believed to be novel and to involve an inventive step under PCT Article 33(2) and 33(3).

### 3) Industrial Applicabilty

And the present invention has industrial applicability under PCT Article 33(4).

### PATENT COOPERATION TREATY

From the INTERNATIONAL SEARCHING AUT	HORITY	•	BEC'D 0.2 AUG 2005
To:			REC'D O 2003 PCT
AN, Sang Jeong			WIPO
512-1906 221, Gumi-dong, Bundang-g Kyunggi-do 463-715 Republic of Kores		WR. INTERNATI	ITTEN OPINION OF THE ONAL SEARCHING AUTHORITY
			(PCT Rule 43bis.1)
	<i>M</i>		
		Date of mailing (day/month/year) 2	22 JULY 2005 (22.07.2005)
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International Patent Classification (IPC)	) or both national classifica	ation and IPC	j
IPC7 H01L 33/00			. 1
Applicant			
LUXELLENT CO., LTD. et a	al		
1. This opinion contains indications re	elating to the following iter	ms:	
Box No. I Basis of the o		•	
Box No. II Priority		•	
Box No. III Non-establish	nment of opinion with rega	rd to novelty, inventive	step and industrial applicability
Box No. IV Lack of unity	of invention	·	
Box No. V Reasoned sta	tement under Rule 43bis. 1 explanations supporting su	(a)(i) with regard to no ach statement	velty, inventive step or industrial applicability;
Box No. VI Certain docu			
Box No. VII Certain defe	ects in the international app	olication	
] [	rvations on the internations		
International Preliminary Examining other than this one to be the IPEA opinions of this International Search	ng Authority ("IPEA") exc and the chosen IPEA has r ching Authority will not be	notified the International so considered.	considered to be a written opinion of the pply where the applicant chooses an Authority al Bureau under Rule 66.1bis(b) that written
If this opinion is, as provided above IPEA a written reply together, who of Form PCT/ISA/220 or before the For further options, see Form PCT	ere appropriate, with amen ne expiration of 22 months	aments, delote the exp	the applicant is invited to submit to the iration of 3 months from the date of mailing whichever expires later.
3. For further details, see notes to Fo	orm PCT/ISA/220.	•	
1			

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KIM, Dong Yup



International application No.
PCT/KR2005/000895

Box	No. I Basis of this opinion
	With regard to the language, this opinion has been established on the basis of the international application in the language in which it was filed, unless otherwise indicated under this item.  This opinion has been established on the basis of a translation from the original language into the following language
	, which is the language of a translation furnished for the purposes of international search (under Rules 12.3 and 23.1(b)).
	With regard to any nucleotide and/or amino acid sequence disclosed in the international application and necessary to the claimed invention, this opinion has been established on the basis of:
	a. type of material  a sequence listing  table(s) related to the sequence listing
	b. format of material in wirtten format in computer readable form
	c. time of filing/furnishing  contained in the international application as filed.  filed together with the international application in computer readable form.  furnished subsequently to this Authority for the purposes of search.
3.	In addition, in the case that more than one version or copy of a sequence listing and/or table relating thereto has been filed or furnished, the required statements that the information in the subsequent or additioanl copies is identical to that in the application as filed or does not go beyond the application as filed, as appropriate, were furnished.
4.	Additional comments:

International application No. PCT/KR2005/000895

Box No. V Reasoned statement under Rule 43bis.1(a)(i) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

Novelty (N)	Claims 1-20	YES
	Claims NONE	NO
Inventive step (IS)	Claims 1-20	YES
	Claims NONE	NO
Industrial applicability (IA)	Claims 1-20	YES
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- continued -

International application No.

PCT/KR2005/000895

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Continuation of:

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